What is claimed is:

- 1. A transparent resin film for an electronic display, wherein the transparent resin film has an ultraviolet light transmittance of not less than 50%, the ultraviolet light having a wavelength range of from 250 to 450 nm, and has a glass transition temperature of not less than 180 °C, the glass transition temperature being measured according to thermal stress strain measurement (TMA).
- 2. The transparent resin film of claim 1, wherein the transparent film contains a cellulose ester as a main component.
- 3. The transparent resin film of claim 1, wherein the transparent film contains a cellulose ester and a hydrolytic polycondensation product of an alkoxysilane represented by the following formula 1,

Formula 1

 (R_{4-n}) Si $(OR')_n$

wherein R and R' independently represent a hydrogen atom or a substituent; and n represents an integer of 3 or 4.

4. The transparent resin film of claim 2, wherein a degree of substitution in the cellulose ester satisfies the following expressions 1 and 2:

Expression 1

6314

 $0 \le Y \le 1.5$

Expression 2

 $1.0 < Y \le 2.9$

wherein X represents a degree of substitution of an acetyl group, and Y represents a degree of substitution of a substituent having an alkoxysilyl group.

5. The transparent resin film of claim 3, wherein the content of the hydrolytic olycondensation product is less than 20% by weight based on the transparent film, and wherein the hydrolytic polycondensation product is represented by the following formula 2,

Formula 2

 (R_{4-n}) SiO_{n/2}

wherein R represents a hydrogen atom or a substituent; and n represents an integer of 3 or 4.

- 6. The transparent resin film of claim 1, wherein the transparent film contains a plasticizer in an amount of less than 1% by weight.
- 7. The transparent resin film of claim 1, wherein the ratio R_0 (480)/R (590) obtained by dividing retardation in plane R_0 (480) of the film at a wavelength 480 nm by retardation in plane R (590) of the film at a wavelength 590 nm is from 0.8 to less than 1.0.

8. The transparent resin film of claim 3, wherein the transparent film contains the cellulose ester in an amount of not less than 80% by weight and the hydrolytic polycondensation product in an amount of 1 to less than 20% by weight in terms of silicon dioxide.

- 9. A transparent conductive film comprising the transparent resin film of claim 1, wherein a moisture proof layer containing a metal oxide, a metal nitride or a metal carbide is provided on one side of the transparent resin film and a transparent conductive layer is provided on the moisture proof layer or on the other side of the transparent resin film.
- 10. The transparent conductive film of claim 9, wherein the transparent conductive layer is provided on the moisture proof layer and on the other side of the transparent resin film.
- 11. The transparent conductive film of claim 9, wherein the moisture proof layer is comprised mainly of silicon oxide.
- 12. The transparent conductive film of claim 10, wherein the moisture proof layer is comprised mainly of silicon oxide.

13. The transparent conductive film of claim 9, wherein the moisture proof layer is amorphous.

- 14. The transparent conductive film of claim 9, wherein the moisture proof layer or the transparent conductive layer is formed by inducing electric discharge between two opposed electrodes at atmospheric pressure or at approximately atmospheric pressure by applying high frequency voltage across the two opposed electrodes to excite a reactive gas between the two opposed electrodes to a plasma state, and the exposing the transparent resin film to the reactive gas of the plasma state.
- 15. The transparent conductive film of claim 14, wherein a frequency of the high frequency voltage is from 100 kHz to 150 MHz, and an output power supplied is from 1 to 50 W/cm^2 .
- 16. A liquid crystal display comprising, as a substrate, the transparent conductive film of claim 9.
- 17. An organic EL display comprising, as a substrate, the transparent conductive film of claim 9.
- 18. A touch panel comprising, as a substrate, the transparent conductive film of claim 9.
- 19. A method of manufacturing the transparent resin film of claim 1 according to a solution cast method.